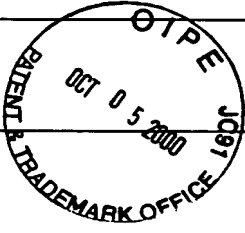


Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		DOCKET NO. 8229-006-27		SERIAL NO. 09/609,387	
LIST OF REFERENCES CITED BY APPLICANT (Use Several Sheets if Necessary)				APPLICANT T. FRANK WANG			
				FILING DATE JULY 3, 2000		GROUP ART UNIT 1765	
							
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>h</i>	AA	4,923,562	5/8/90	JUCHA ET AL.			
<i>h</i>	AB	5,100,505	3/31/92	CATHEY, JR.			
<i>h</i>	AC	5,143,866	9/1/92	MATSUTANI			
<i>h</i>	AD	5,609,775	3/11/97	LIU			
<i>h</i>	AE	5,772,906	6/30/98	ABRAHAM			
<i>h</i>	AF	5,846,443	12/8/98	ABRAHAM			
<i>h</i>	AG	5,853,602	12/29/98	SHOJI			
<i>h</i>	AH	5,952,244	9/14/99	ABRAHAM, ET AL.			
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>h</i>	AO	DAVID A. SHUMATE, ET AL., "DEVELOPMENT OF A TiW PLASMA ETCH PROCESS USING A MIXTURE EXPERIMENT AND RESPONSE SURFACE OPTIMIZATION", IEEE TRANSACTIONS ON SEMICONDUCTOR MANUFACTURING, VOL. 9 NO. 3, AUGUST 1996.					
	AP						
	AQ						
EXAMINER <i>Theresa A. - for</i>					DATE CONSIDERED 10/20/01		
<p>*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.</p>							

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